

	Type	Hits	Search Text	DBs
1	BRS	16	epitaxial and laser and (multiple adj quantum adj wells MQW) and DBR and ((thinning narrowing etching) with substrate)	USPAT; US-PGPUB; EPO
2	BRS	1	epitaxial and (multiple adj quantum adj wells MQW) and DBR and ((thinning narrowing etching) with substrate) and (oxidation oxidize) and solder	USPAT; US-PGPUB; EPO
3	BRS	1	(multiple adj quantum adj wells MQW) and DBR and ((thinning narrowing etching) with substrate) and (oxidation oxidize) and solder	USPAT; US-PGPUB; EPO
4	BRS	6	(multiple adj quantum adj wells MQW) and ((thinning narrowing etching) with substrate) and (oxidation oxidize) and solder	USPAT; US-PGPUB; EPO
5	BRS	4	("5376580" "5491712" "5502316" "5606572").PN.	USPAT
6	BRS	11	(multiple adj quantum adj wells MQW) and (thinning with substrate) and (oxidation oxidize)	USPAT; US-PGPUB; EPO
7	BRS	0	(multiple adj quantum adj wells MQW) and (induced adj evaporation adj enhancement) and (oxidation	USPAT; US-PGPUB; EPO
8	BRS	225	(multiple adj quantum adj wells MQW) and VCSEL and DBR and mirror	USPAT; US-PGPUB; EPO
9	BRS	2194	thinning with substrate	USPAT; US-PGPUB; EPO
10	BRS	739	(thinning with substrate) and (laser SEL VCSEL)	USPAT; US-PGPUB; EPO
11	BRS	730	((thinning with substrate) and (laser SEL VCSEL)) not ((multiple adj quantum adj wells MQW) and VCSEL and DBR and mirror)	USPAT; US-PGPUB; EPO
12	BRS	73	((thinning with substrate) and (laser SEL VCSEL)) not ((multiple adj quantum adj wells MQW) and VCSEL and DBR and mirror)) and (quantum adj well QW MQW)	USPAT; US-PGPUB; EPO
13	BRS	161	substrate near3 remnant	USPAT; US-PGPUB; EPO
14	BRS	4	(substrate near3 remnant) and (quantum adj well QW MQW)	USPAT; US-PGPUB; EPO